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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
10/606,834	06/27/2003	Kouji Nakahara	NIT-379 4822		
75	590 11/03/2004	EXAMINER			
Mattingly, Stanger & Malur, P.C.			DICKEY, THOMAS L		
Suite 370 1800 Diagonal l	Road	ART UNIT	PAPER NUMBER		
Alexandria, VA 22314			2826		
			DATE MAILED: 11/03/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application	n No.	Applicant(s) NAKAHARA ET AL.			
		10/606,83	4				
Office Action Summary		Examiner		Art Unit			
		Thomas L	Dickey	2826			
Period fo	The MAILING DATE of this communication a or Reply	appears on the	cover sheet with the d	orrespondence add	iress		
THE - Exte after - If the - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REF MAILING DATE OF THIS COMMUNICATION nsions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication. e period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period to reply within the set or extended period for reply will, by state reply received by the Office later than three months after the may be aptent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no evereply within the statuod will apply and will tute, cause the apple	nt, however, may a reply be tin tory minimum of thirty (30) day I expire SIX (6) MONTHS from cation to become ABANDONE	nely filed s will be considered timely. the mailing date of this cor (35 U.S.C. § 133).			
Status							
1)	Responsive to communication(s) filed on 14	September 2	004.				
<u> </u>	This action is FINAL . 2b)⊠ This action is non-final.						
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Dispositi	on of Claims						
5)□ 6)⊠ 7)⊠	Claim(s) <u>1-20</u> is/are pending in the application 4a) Of the above claim(s) is/are withd Claim(s) is/are allowed. Claim(s) <u>1,2 and 12-20</u> is/are rejected. Claim(s) <u>3-11</u> is/are objected to. Claim(s) are subject to restriction and	rawn from cor					
Applicati	on Papers						
10)⊠	The specification is objected to by the Exami The drawing(s) filed on 27 June 2003 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction of the oath or declaration is objected to by the	a) accepte he drawing(s) be ection is require	e held in abeyance. Seed if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFf	` '		
Priority u	ınder 35 U.S.C. § 119						
12)⊠ a)[Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the priority docume application from the International Bure see the attached detailed Office action for a light	ents have beer ents have beer riority docume eau (PCT Rule	n received. n received in Applications nts have been received the 17.2(a)).	on No ed in this National S	Stage		
Attachment							
	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948)		4) Interview Summary Paper No(s)/Mail Da	•			
3) Inform	nation Disclosure Statement(s) (PTO-1449 or PTO/SB/0 r No(s)/Mail Date)8)	5) Notice of Informal P 6) Other:		152)		

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DETAILED ACTION

1. The amendment filed 8/19/04 has been entered.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1,2, and 12-20 are rejected under 35 U.S.C. § 103(a) as being unpatentable over SALVATORE et al. (2002/0131466) in view of MURAI et al. ("Lasing characteristics under high temperature operation of 1.55 µm strained InGaAsP/InGaAlAs MQW laser with InAlAs electron stopper layer", Electronics Letters, Volume 31, Issue 24).

With regard to claims 1,12,14,16,18, and 19, Salvatore et al. discloses an optical semiconductor device, being an integrated light source in which a buried ridge type laser structure and an electro-absorption modulator are integrated, comprising an InP substrate 16; a plurality of layers 28-30-32-34-18, stacked on the InP substrate 16, including a multi-quantum well active layer 18 made of GalnAlAs; an GalnAlAs electron-stopping layer 36 (Salvatore et al. calls this layer a "upper carrier confinement layer," note paragraph 0026. Note further that Salvatore et al. explicitly states, in said

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paragraph, that the "upper carrier confinement layer" 36 confines electrons but not light) stacked on the plurality of layers 28-30-32-34-18; an InGaAsP layer 20 including a grating stacked on the GaInAlAs electron-stopping layer 36; wherein a concave depth of the grating included in the InGaAsP layer 20 is smaller than a thickness of the InGaAsP layer 20, an InP cladding layer 38, having the shape of a ridge mesa stripe (InP cladding layer 38 has the same ridge mesa stripe structure as waveguide 22, note figures 1 and 15b), stacked on the InGaAsP layer 20.

With regard to claims 2,13,15,17, and 20, Salvatore et al. discloses an optical semiconductor device, being an integrated light source in which a buried ridge type laser structure and an electro-absorption modulator are integrated, comprising an InP substrate 16; a plurality of layers 28-30-32-34-18, stacked on the InP substrate 16, including a multi-quantum well active layer 18 made of GalnAlAs; an GalnAlAs electron-stopping layer 36 (Salvatore et al. calls this layer a "upper carrier confinement layer," note paragraph 0026. Note further that Salvatore et al. explicitly states, in said paragraph, that the "upper carrier confinement layer" 36 confines electrons but not light. Applicant has made it clear that the electron stopping layer must allow light to reach the grating from the active layer) stacked on the plurality of layers 28-30-32-34-18; an InGaAsP layer 20 including a grating stacked on the GalnAlAs electron-stopping layer 36; wherein a concave depth of the grating included in the InGaAsP layer 20 is smaller than a thickness of the InGaAsP layer 20, an InP spacer layer (no part #, described at paragraph 0027 as the upper of the InP layers in an InP/InGaAsP/InP structure) stacked

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on the InGaAsP layer 20; an InGaAsP etch stopping layer 44 stacked on the InP spacer layer; and an InP cladding layer 46, having the shape of a ridge mesa stripe (InP cladding layer 46 has the same ridge mesa stripe structure as waveguide 22, note figures 1 and 15b), stacked on the InGaAsP etch stopping layer 44.

Note figures 1,2, 15b, and paragraphs 0004-0010 and 0025-0029 of Salvatore et al. Although Salvatore et al. discloses a GaAllnAs electron-stopping layer, Salvatore et al. does not disclose an InAlAs electron-stopping layer. However, Murai et al. discloses an InAlAs electron-stopping layer, note figure 1 of Murai et al. Note also that Murai et al. teaches that because InAlAs has a significant band offset relative to both GaInAlAs and InGaAsP, the result is both an increase in quantum efficiency and a consequent decrease in laser operating temperature. Therefore, it would have been obvious to a person having skill in the art to replace the GaInAsP active layer of Salvatore et al.'s optical semiconductor device with the InAlAs electron-stopping layer such as taught by Murai et al. in order to raise the band offset between the electron-stopping layer and the active region and better confine electrons to the active region to thus increase quantum efficiency and decrease laser operating temperature.

Allowable Subject Matter

3. Claims 3-11 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

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Response to Arguments

4. Applicant's arguments with respect to claims 1,2,4,5, and 10-18 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thomas L Dickey whose telephone number is 571-272-1913. The examiner can normally be reached on Monday-Thursday 8-6.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan J Flynn can be reached on 571-272-1915. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

TLD 10/2004

Minhloan Tran
Primary Examiner
Art Unit 2826

ckuhlon Tom